

Notice of Allowability	Application No.	Applicant(s)	
	10/768,090	YOSHIDA ET AL.	
	Examiner Thinh T. Nguyen	Art Unit 2818	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. This communication is responsive to 3/24/2005.
2. The allowed claim(s) is/are 6-14.
3. The drawings filed on 02 February 2004 are accepted by the Examiner.
4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some* c) None of the:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) hereto or 2) to Paper No./Mail Date _____.
 - (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. Notice of References Cited (PTO-892)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)
3. Information Disclosure Statements (PTO-1449 or PTO/SB/08),
Paper No./Mail Date _____
4. Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. Notice of Informal Patent Application (PTO-152)
6. Interview Summary (PTO-413),
Paper No./Mail Date _____
7. Examiner's Amendment/Comment
8. Examiner's Statement of Reasons for Allowance
9. Other _____.



David Nelms
Supervisory Patent Examiner
Technology Center 2800

DETAILED ACTION

Examiner's Amendment.

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee. Change the title to:

-- METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE --

Specification

2. The specification has been checked to the extent necessary to determine the presence of all possible minor errors. However, the applicant cooperation is requested in correcting any errors of which the applicant may become aware in the specification.

Reason for allowance

3. Claims 6-14 are allowed. The following is an examiner's statement of reason for allowance:

I/ Group I: Claims 6-10:

Claims 6-9 are allowed because none of the references of record teaches or suggests the claimed **METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE** having the steps limitations:

-- " forming over a semiconductor substrate a first dielectric film of

$Hf_x Al_{1-x} O_y$ in which x is $0.7 < x < 1$;

forming a second dielectric film different from the first dielectric film over the first dielectric film"--

and all other limitations as recited in claim 6.

II/ Group II: Claims 11-14:

Claims 11-14 are allowed because none of the references of record teaches or suggests the claimed **METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE** having the steps limitations:

-- "forming first dielectric film of silicon-based insulating film semiconductor substrate;

forming over the first dielectric film second dielectric film of $Hf_x Al_{1-x} O_y$ having a thickness below 1 nm in which $0.7 < x < 1$;"--

and all other limitations as recited in claim 11.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

4. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d) which papers have been placed of record in the file.

Conclusion

5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Halliayal et al. (US patent 6,451,641) disclose a non-reducing process for deposition of polysilicon gate electrode over high -k gate dielectric material.

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thinh T Nguyen whose telephone number is 571-272-1790. The examiner can normally be reached on Monday-Friday 9:00am-6:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached at 571-272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9319 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application
or proceeding should be directed to the receptionist whose telephone number is
(703) 308-0956.

Thinh T Nguyen *TTN*

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David Neims
Supervisory Patent Examiner
Technology Center 2800